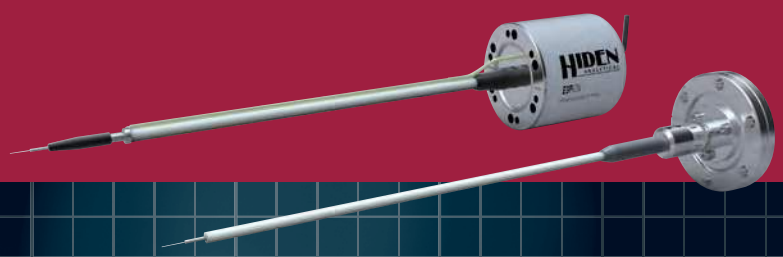
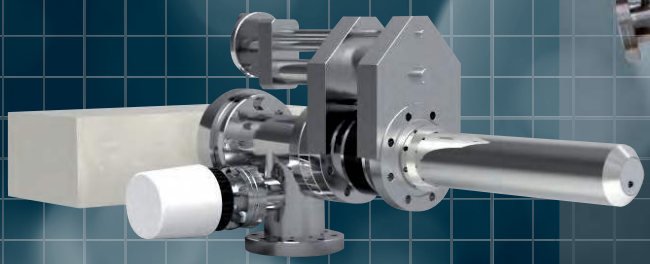
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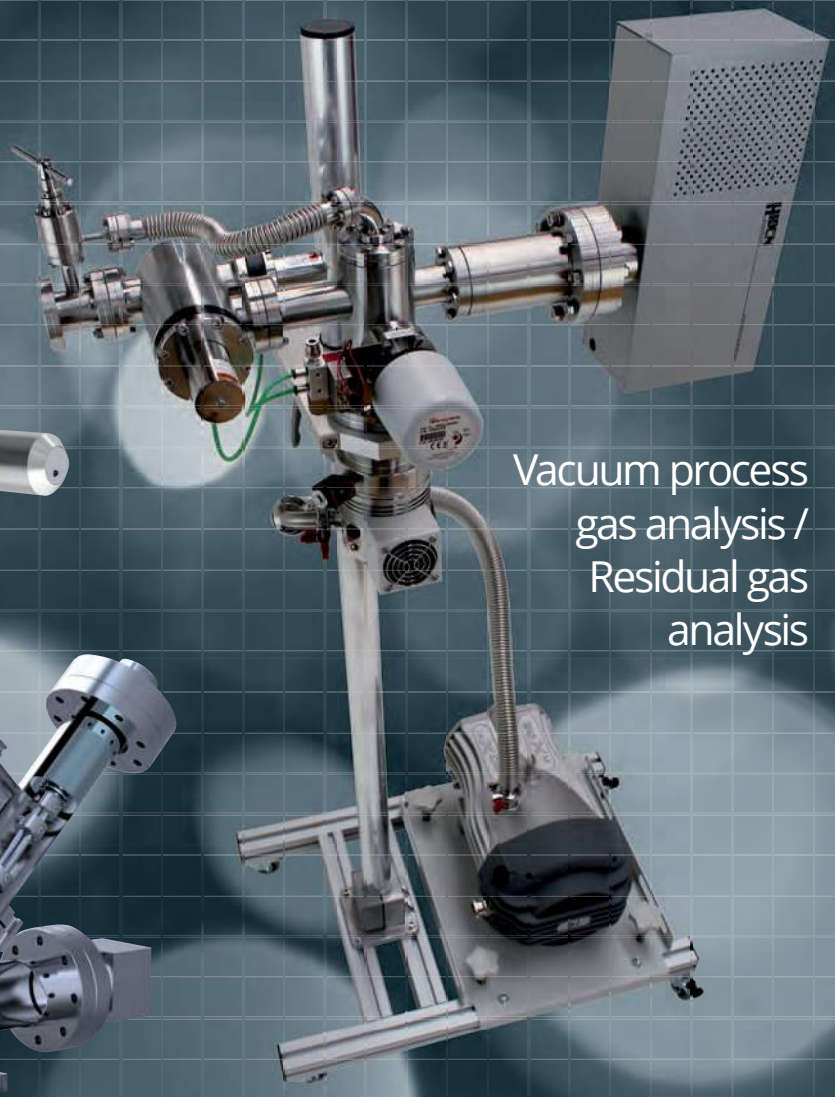


Plasma Etch
IN MICROTECHNOLOGY

Advanced Langmuir probe for plasma diagnostics

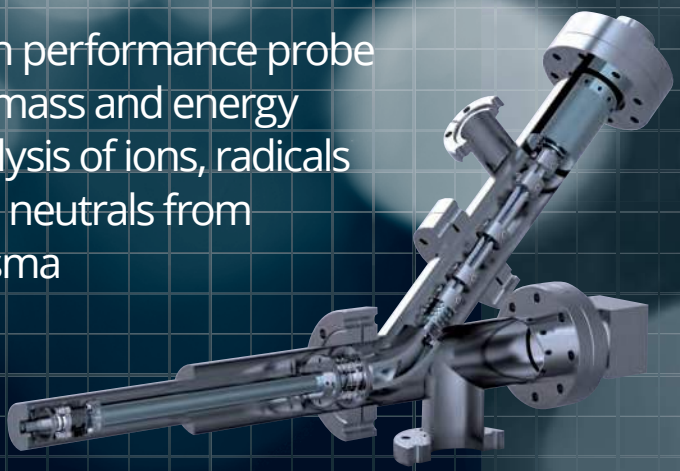
In-situ SIMS analysers for real-time etch monitoring at the nanoscale



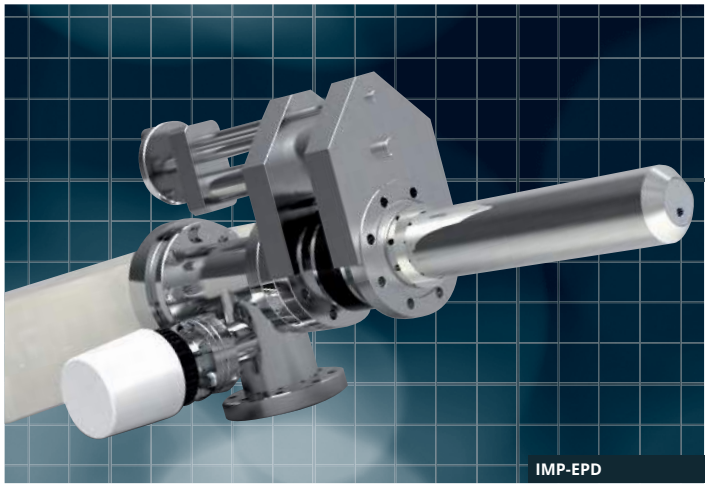


Vacuum process gas analysis / Residual gas analysis

High performance probe for mass and energy analysis of ions, radicals and neutrals from plasma

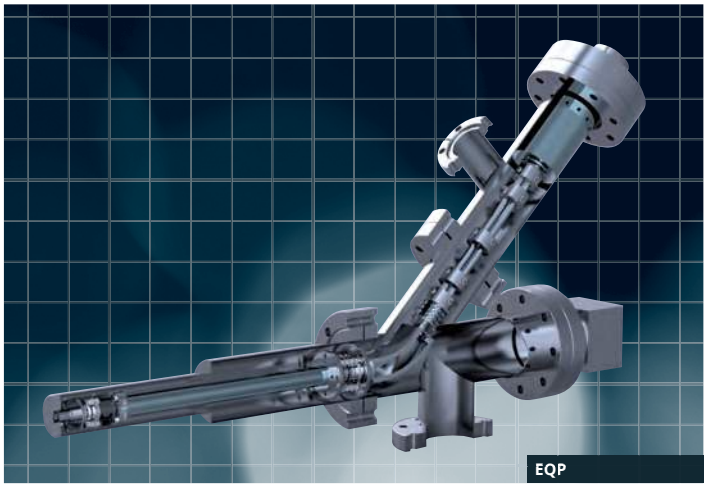


W www.HidenAnalytical.com E info@hiden.co.uk


IMP-EPD

In-situ SIMS analysers for real-time etch monitoring at the nanoscale

- Hiden SIMS plasma and ion beam etch analysers provide a window on the entire etch process
- End point control to within +/- 5 Angstroms
- Integrated 'production ready' end point control is available


EQP

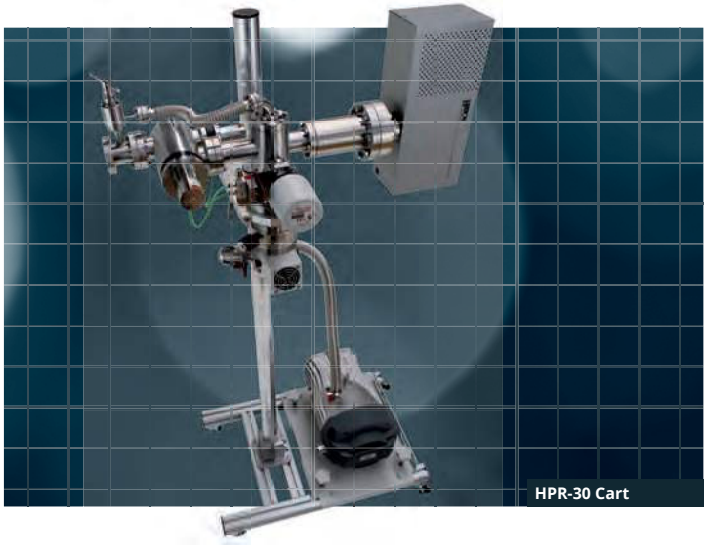
High performance probe for mass and energy analysis of ions, radicals and neutrals from plasma

- +ve and –ve ion analysis
- Mass resolved ion energy analysis
- Neutrals and neutral radical analysis
- Energy resolved mass analysis
- Mass range options to 1000 amu
- Energy range options to 1000 eV


ESPion

Advanced Langmuir probe for plasma diagnostics

- Floating Potential, V_f
- Plasma Potential, V_p
- Electron Energy Distribution Function, EEDF
- Debye length, λ_D
- Ion Flux, Γ_i
- Ion density, n_i, and electron density, n_e, over the range 10^{14}-10^{19} m^{-3}
- Electron Temperature, T_e, up to 10 eV
- Orbital Motion Limited (OML) and Allen Boyd Reynolds (ABR)


HPR-30 Cart

Vacuum process gas analysis / Residual gas analysis

- Pump-down Profiles
- Vacuum Diagnostics
- Base Pressure
- Residuals
- Backfill
- Bakeout
- Leak Checking

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